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Page 1 of 1 Atty. Docket No. Serial No. 97-0008D1 10/015,434 List of Patents and Publications for Applicant's Applicant Bradley J. Howard PRIMATION DISCLOSURE STATEMENT Filing Date: Group:

MAR 1 4 2002 (Use several sheets if necessary)

December 13, 2001

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Patent Documents See Page 1

Form PTO-1449 (modified)

Foreign Patent Documents See Page 1

Other Art See Page 1

## **U.S. Patent Documents**

Exam Init.	Ref.	Document Number	Date Williams	Name (	Class	Sub Class	Filing Date if App.
KN.	Al	4,921,321	5/1/90	Weidman	Signer Signer	* \$1.50 \$4.50 \$1.50 \$4.50	大学の大学を
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## Foreign Patent Documents

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## Other Art (Including Author, Title, Date Pertinent Pages, Etc.

Exam.	Ref. Des.	Citation
K.N.	Ĉ	Ajey M. Joshi et al., "Plasma Deposited Organosilicon Hydridge Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV Photolithography," SPIE, Vol. 1925, pp. 709—720, January 1993.
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